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### ACCEPTED MANUSCRIPT

# Fabrication and gas sensing properties of vertically aligned Si nanowires

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#### Highlights

- Novel configuration for a gas sensor consisting of vertically aligned silicon nanowires synthesized by metal-assisted chemical etching.
- Highly vertically oriented arrays of Si NWs with a straight-line morphology were obtained.
- Vertically aligned silicon nanowires exhibited a remarkable response ( $R_g/R_a = 11.5 \sim 17.1$ )

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